

**Amendments to the Specification:**

Please replace paragraph [0016] with the following amended paragraph:

[0016]        Such a magnetron cathode technology has following problems in a current sputtering process requiring a small line width (0.14 ~~[[ $\mu$ m]]~~  $\mu$ m or less) and high aspect ratio (5:1 or more): deposition occurs asymmetrically, film uniformity is poor, and target erosion occurs locally, thereby decreasing the efficiency of materials used.